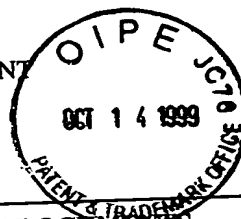


37 CFR 1.501
**INFORMATION DISCLOSURE STATEMENT
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Applicants
Günter Doemens, et al.

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Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If appropriate
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							Yes	No
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Examiner

Colin LaRose

Date Considered

6-24-02

***EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.